Amendments to the Specification:

At page 1, after the title and before the heading "Background," please insert the following paragraph:

--This application is a continuation of U.S. Patent Application Serial No. 09/716,507, filed November 20, 2000; which is a continuation of U.S. Patent Application Serial No. 09/244,568, filed February 4, 1999, now Patent No. 6,307,042; which in turn is a continuation of U.S. Patent Application Serial No. 08/634,053, filed April 17, 1996, now Patent No. 5,959,098; all of which are hereby incorporated herein by reference.--

Please replace the paragraph beginning at page 28, line 17 with the following paragraph:

--A schematic illustration of one embodiment of an integrated reactor system is shown in Figure ~~3C~~ 4C. The device includes an automated peptide synthesizer 401. The automated peptide synthesizer is a device which flows selected reagents through a flow cell 402 under the direction of a computer 404. In a preferred embodiment the synthesizer is an ABI Peptide Synthesizer, model no. 431A. The computer may be selected from a wide variety of computers or discrete logic including ~~for,~~ for example, an IBM PC-AT or similar computer linked with appropriate internal control systems in the peptide synthesizer. The PC is provided with signals from the ABI computer indicative of, for example, the beginning of a photolysis cycle. One can also modify the synthesizer with a board that links the contacts of relays in the computer in parallel with the switches to the keyboard of the control panel of the synthesizer to eliminate some of the keystrokes that would otherwise be required to operate the synthesizer.--

Please replace the paragraph beginning at page 55, line 28 with the following paragraph:

--Figures ~~8A and 8B~~ 9A and 9B illustrate the contrast difference between back-side exposure synthesis and front-side exposure synthesis, respectively. Figure 9A shows a fluorescent scan of a substrate having fluorescent groups coupled directly to the surface of the substrate using photolithographic techniques, with a mask having 50 μm and 100 μm feature sizes where the activating light was shown through the back-side of the substrate. Figure 9B shows the same synthesis where the activation light was directed at the front side of the substrate. The definition of the individual features is greatly enhanced using this front-side photolysis.--

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